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CERTIFICATE OF MAILING

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Tanya Parker

(Typed or Printed Name of Person Mailing Paper or Fee)

Technology Center 2100

Tanya Parker
(Signature of Person Mailing Paper or Fee)

Attorney Docket No.: NMTC-0770

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Inventor: Kevin D. MacLean, et al.
Title: USING SUGGESTED A SOLUTION TO SPEED UP A PROCESS FOR SIMULATING AND CORRECTING AN INTEGRATED CIRCUIT LAYOUT
Filing Date: March 15, 2002
Serial Number: 10/098,714
Group Art Unit: 2123
Examiner: To Be Assigned

Listed below or on an attached Form PTO-1449 is information known to applicant(s) and submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP §609.

This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in §1.56.

X This statement qualifies under 37 C.F.R. §1.97, subsection (b) because (check all that apply):

- (1) It is being filed within 3 months of the application filing date
 -- OR --
 (2) It is being filed within 3 months of entry of a national stage
 -- OR --
X (3) It is being filed before the mail date of the first Office Action on the merits.

— 37 C.F.R. §1.97(c). If this statement is being filed after the latest of: (1) three months beyond the filing date of a national application; (2) three months beyond the date of entry of the national stage as set forth in §1.491 in an international application; or (3) the mailing date of a first Office action on the merits, but before the mailing date of the earlier of a final office action under §1.113 or a notice of allowance under §1.311, then:

— a certification as specified in §1.97(e) is provided below; **or**

— a fee of \$240.00 as set forth in §1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement. Please note that a check in the amount of \$240.00 is enclosed in payment.

— 37 C.F.R. §1.97(d). If this statement is being filed after the mailing date of the earlier of a final office action under §1.113 or a notice of allowance under §1.311, but before payment of the issue fee, then:

A. a certification as specified in §1.97(e) is completed below; **and**

B. a petition under 37 C.F.R. §1.97(d) requesting consideration of this statement is submitted herewith; **and**

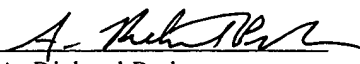
C. a fee of \$130.00 as set forth in §1.17(i)(1) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.

— Statement under 37 C.F.R. §1.97(e) - I hereby certify that either: each item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign patent application not more than three months prior to the filing of the information disclosure statement; or no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign patent application, and, to the knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in section 1.56(c) more than three months prior to the filing of the information disclosure statement.

Signature: _____
A. Richard Park (Reg. No. 41,241)

Date

Respectfully submitted,

By: 
A. Richard Park
Reg. No. 41,241

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Date: July 17, 2002

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CITATION**

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
	5,432,714	7/11/1995	Chung, et al.	364	525	9/2/1994
	5,533,148	7/2/1996	Sayah, et al.	382	240	9/30/1993
	5,538,815	7/23/1996	Oi, et al.	430	5	9/14/1993
	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
	5,657,235	8/12/1997	Liebmann, et al.	364	474.24	5/3/1995
	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
	5,885,734	3/23/1999	Pierrat, et al.	430	5	8/15/1996
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	6,370,679 B1	4/9/2002	Chang, et al.	716	19	9/16/1998
	2002/0010904 A1	1/24/2002	Ayres	716	19	7/23/2001

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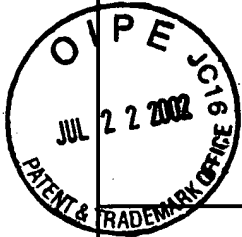
FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 02/29491 A1	4/11/2002	WO			<input type="checkbox"/>	<input type="checkbox"/>
	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>
	WO 97/38381	10/16/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14636 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14637 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14638 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.
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